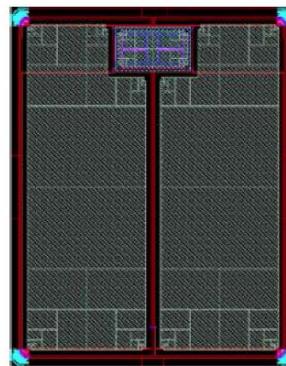


Description

Silicon Carbide (SiC) MOSFET use a completely new technology that provide superior switching performance and higher reliability compared to Silicon. In addition, the low ON resistance and compact chip size ensure low capacitance and gate charge. Consequently, system benefits include highest efficiency, faster operating frequency, increased power density, reduced EMI, and reduced system size.

Features

- High Speed Switching with Low Capacitances
- High Blocking Voltage with Low RDS(on)
- Easy to parallel and simple to drive
- ROHS Compliant, Halogen free

**Application**

- EV motor drive
- High Voltage DC/DC Converters
- Switch Mode Power Supplies
- Solar inverters
- EV charging

Absolute Maximum Ratings(Tc=25 °C)

Symbol	Parameter	Value	Unit
V _{DS}	Drain-Source Voltage	1200	V
I _D	Drain Current(continuous)at Tc=25 °C	115	A
I _D	Drain Current(continuous)at Tc=100 °C	85	A
I _{DM}	Drain Current (pulsed)	250	A
V _{GS}	Gate-Source Voltage	-10/+22	V
P _D	Power Dissipation T _c = 25 °C	550	W
T _J , T _{Stg}	Junction and Storage Temperature Range	-55 to +175	°C

Electrical Characteristics(T_J = 25 °C unless otherwise specified)**Typical Performance-Static**

Symbol	Parameter	Test Conditions	Min.	Typ.	Max.	Unit
BV _{DS}	Drain-source Breakdown Voltage	I _D =250uA, V _{GS} =0V	1200			V
I _{DSS}	Zero Gate Voltage Drain Current	V _{DS} =1200V, V _{GS} =0V, T _J =25 °C			100	uA
I _{GSS}	Gate-body Leakage Current	V _{DS} =0V ; V _{GS} =-10 to 20V			250	nA
V _{GS(th)}	Gate Threshold Voltage	V _{DS} = V _{GS} , I _D =22mA	2	3	4	V
V _{GSon}	Recommended turn-on Voltage	Static		20		V
V _{GSoff}	Recommended turn-off Voltage			-5		V
R _{DSON}	Static Drain-source On Resistance	V _{GS} =20V, I _D =50A		16	22	mΩ
		V _{GS} =20V, I _D =50A T _J =175 °C		25.2		mΩ

Mechanical Parameters

Parameter	Typical Value	Unit
Die Dimensions (L×W) without scribe line	5.000×6.308	mm
Gate Pad Dimensions (L×W)	1.18×0.6	mm
Source Pad Metal Dimensions (LxW) Each	$2.038 \times 5.690 \times 2$	mm
Scribe Line	80	um
Die Thickness	175 ± 20	um
Top Side Source metallization (Al)	4	um
Top Side Gate metallization (Al)	4	um
Bottom Drain metallization (Ti/Ni/Ag)	0.2/0.3/2	um

Chip Dimensions